

# Fully Automatic Grinder DFG8830



## Pioneering a new stage for processing hard and brittle materials

# Support for the grinding of hard and brittle materials

The DFG8330 is equipped with a highly durable and high power spindle for large diameter grinding wheels for the fully automatic processing of high-load hard and brittle workpieces.

#### 4-axis, 5-chuck table configuration

The 4-axis, 5-chuck table, and 1 turntable configuration offers solutions for a variety of applications.

By selecting the optimal wheel for each of the 4 axes, this unit offers for low-damage, high-quality or high-productivity processing for a wide range of applications.



#### **Grinding of wafers with supporting substrates**

The DFG8830 supports the grinding of workpieces with  $\emptyset 5$  - 8-inch glass or ceramic support substrates up to a total thickness of 3.5 mm.

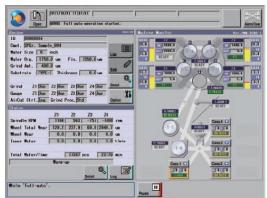
#### **Small footprint**

Optimal arrangement of the spindles and handling systems has resulted in a compact footprint of 3.5  $\,$ m $^{\circ}$ , despite boasting an all-in-one, 4-axis, 5-chuck table configuration.

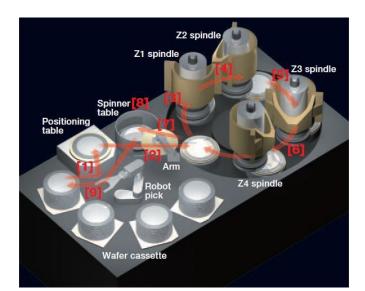
#### **User friendly operation**

The intuitive icon-based GUI touch panel allows simple operation and onscreen step-by-step visualization of the processing stages.

Also, with support for up to four cassettes, the cassette replacement frequency and equipment operation workload can be reduced.



Control screen



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#### **DFG8830 Operation flow**

- [1] The robot pick removes the wafer from the cassette and places it on the positioning table, where centering takes place.
- [2] The transfer arm places the wafer on the chuck table.
- [3] [6] Grinding
- [7] The transfer arm removes the wafer from the chuck table and places it on the spinner.
- [8] Cleaning and drying
- [9] The robot pick returns the workpiece to the cassette.

Specification			
Specification		Unit	
Wafer Diameter		-	φ 4" –φ 6"
Substrate Diameter		-	ф 5" –ф 8"
Grinding Method			In-feed grinding with wafer
			Rotation
Grinding Wheels		mm	φ 300 Diamond Wheel
Spindle	Rated Output	kW	6.3
	Rated torque range	min <sup>-1</sup>	1,000 - 4,000
Grinding Accuracy	Thickness variation	μm	3 or less
	within one wafer		
	Thickness variation		±3 or less
	between wafers		
Machine dimensions(WxDxH)		mm	$1,400 \times 2,500 \times 2,000$
Machine weight		kg	Approx.6,000

#### **Environmental conditions**

- Use clean, oil-free air at a dew point of -15 ° C or less. (Use a residual oil: 0.1 ppm. Filtration rating:0.01 µm/99.5 % or more).

  Keep room temperature fluctuations within ±1 ° C of the set value. (Set value should be between 20 25 ° C).

  Keep grinding water and cleaning water +0 2 ° C above room temperature (fluctuations within 1 ° C over one hour).

  Keep spindle cooling water temperature between 20 25 ° C (fluctuations within 2 ° C over an hour).

  The machines should be used in an environment, free from external vibration. Do not install machine near a ventilation opening, heat generation equipment or oil mist generating parts.
- This machine uses water.
- In case of water leakage, please install the machine on the floor with sufficient waterproofing and drainage treatments. All the pressures are described using gauge pressures.
- The above specifications may change due to technical modifications. Please confirm when placing your order. For further information please contact your local sales representatives.